

# Compact Modeling for RF and Microwave Integrated Circuits

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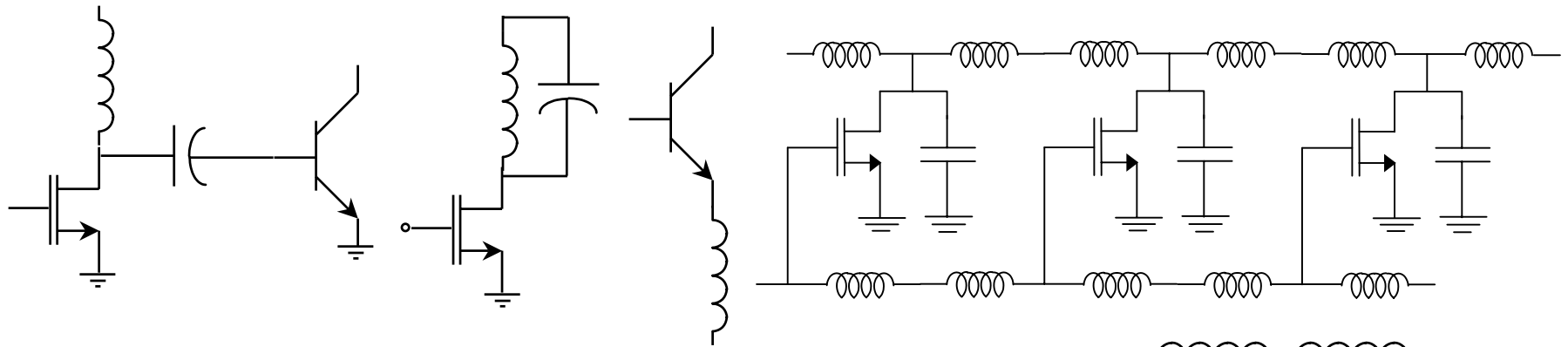
**BSIM**



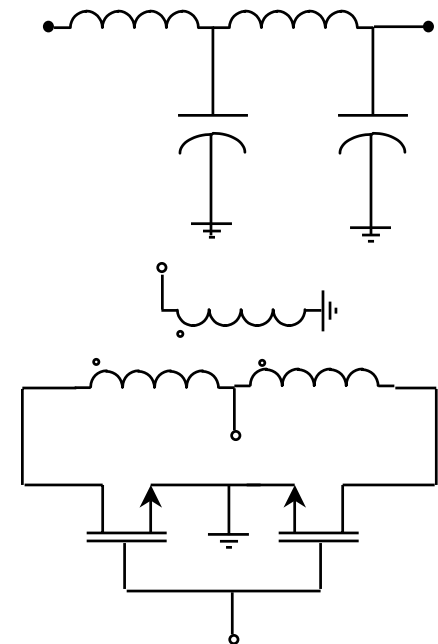
# Outline

- RF and Microwave Applications
- Insights from Maxwell's Equations
- Inductors and Transformers
- Capacitors and Varactors
- Transmission Lines and Resistors
- Substrate Coupling, IC Interconnect
- Package and PCB Modeling
- Active Device Modeling

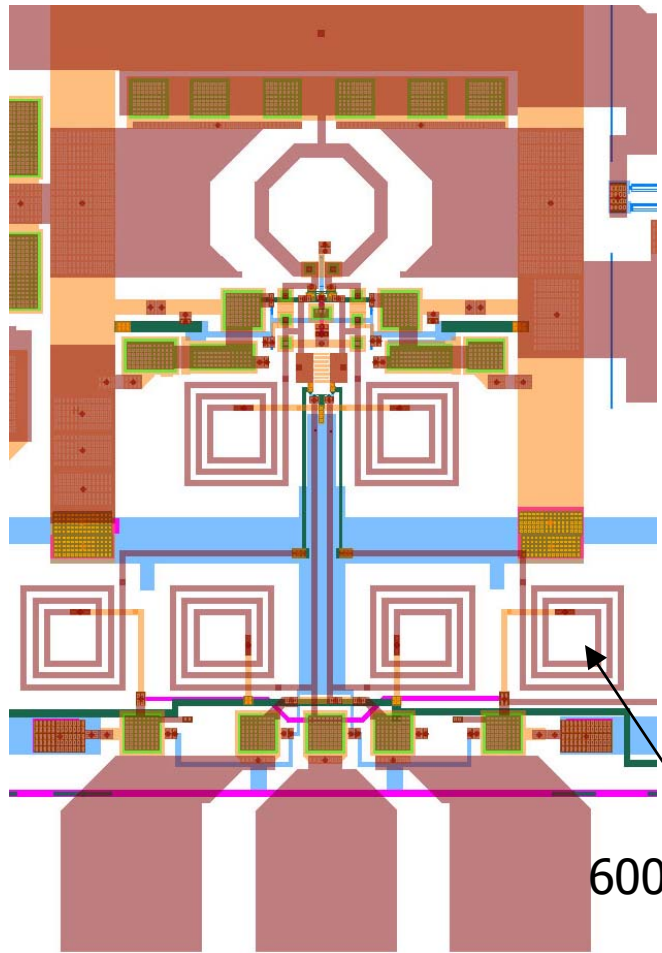
# Applications of Compact Models



- Narrow-band impedance matching
- Tuned loads (resonant tank)
- Low noise degeneration and feedback
- Linear filters (high dynamic range)
- Fully differential circuits
- Artificial transmission lines
- Low voltage/low power design



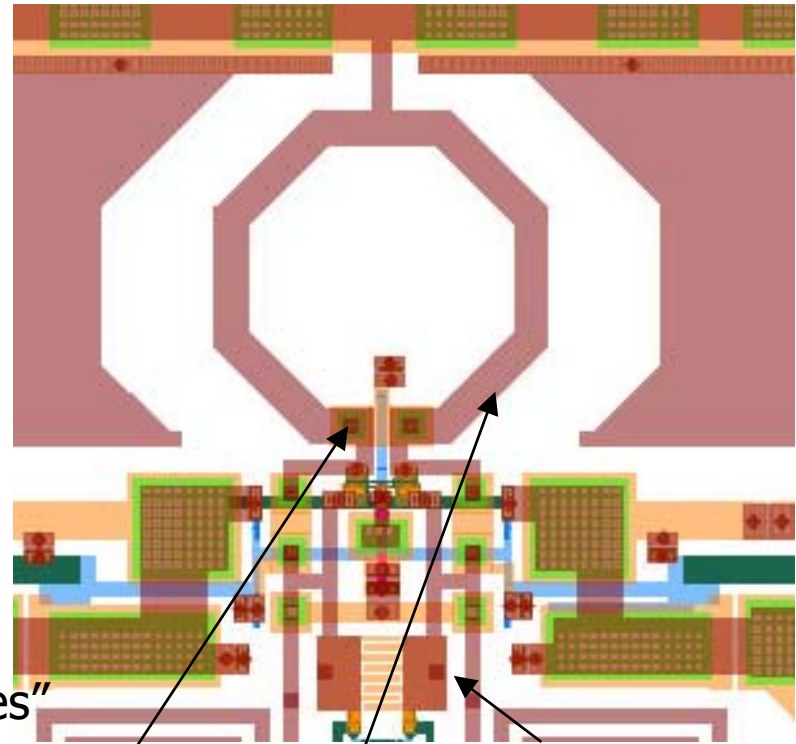
# “RF” Compact Modeling



600 pH "Chokes"

- 55 GHz Oscillator Layout
- Passives “Lumped”

Low Loss MIM Cap and Inductor Ring  
Tightly Coupled for Low Loss

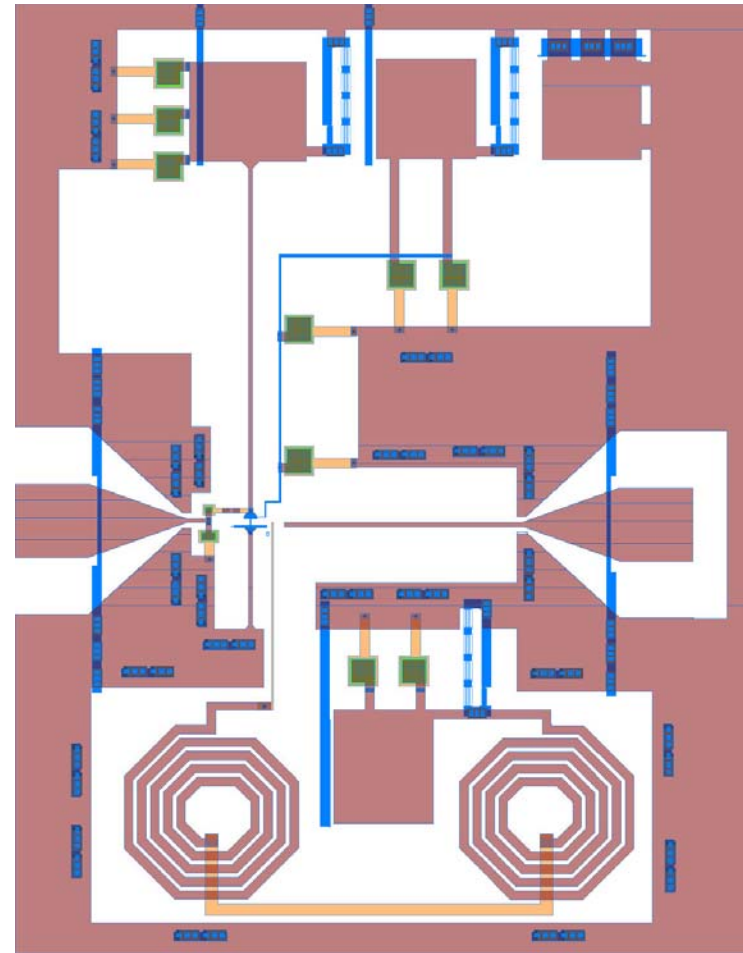
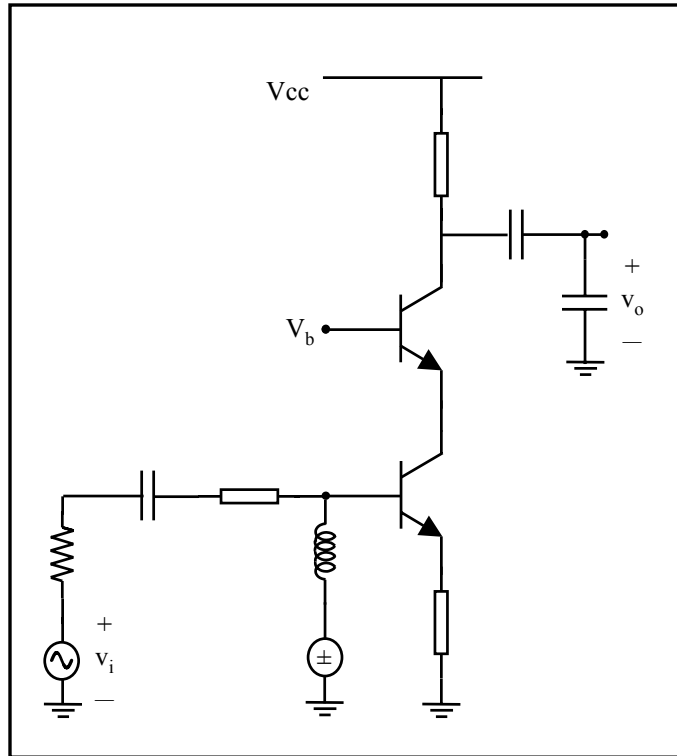


Tank MIM

Low-Loss Custom  
Cap Divider

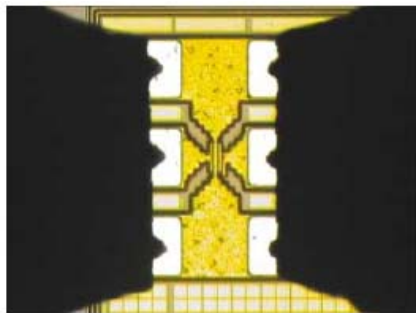
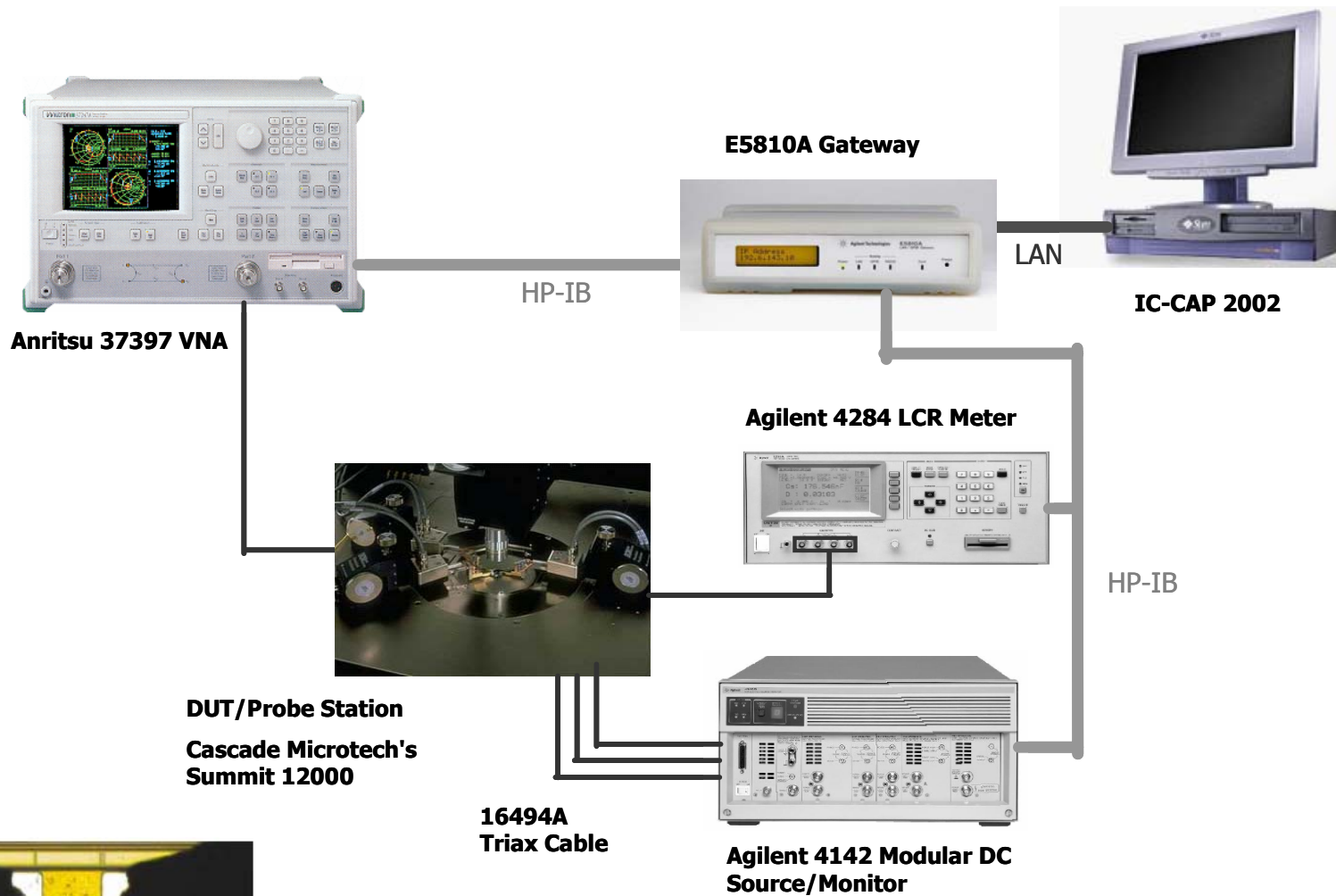
150 pH Loop  
 $Q > 30$  (HFSS)

# “Microwave” Compact Modeling



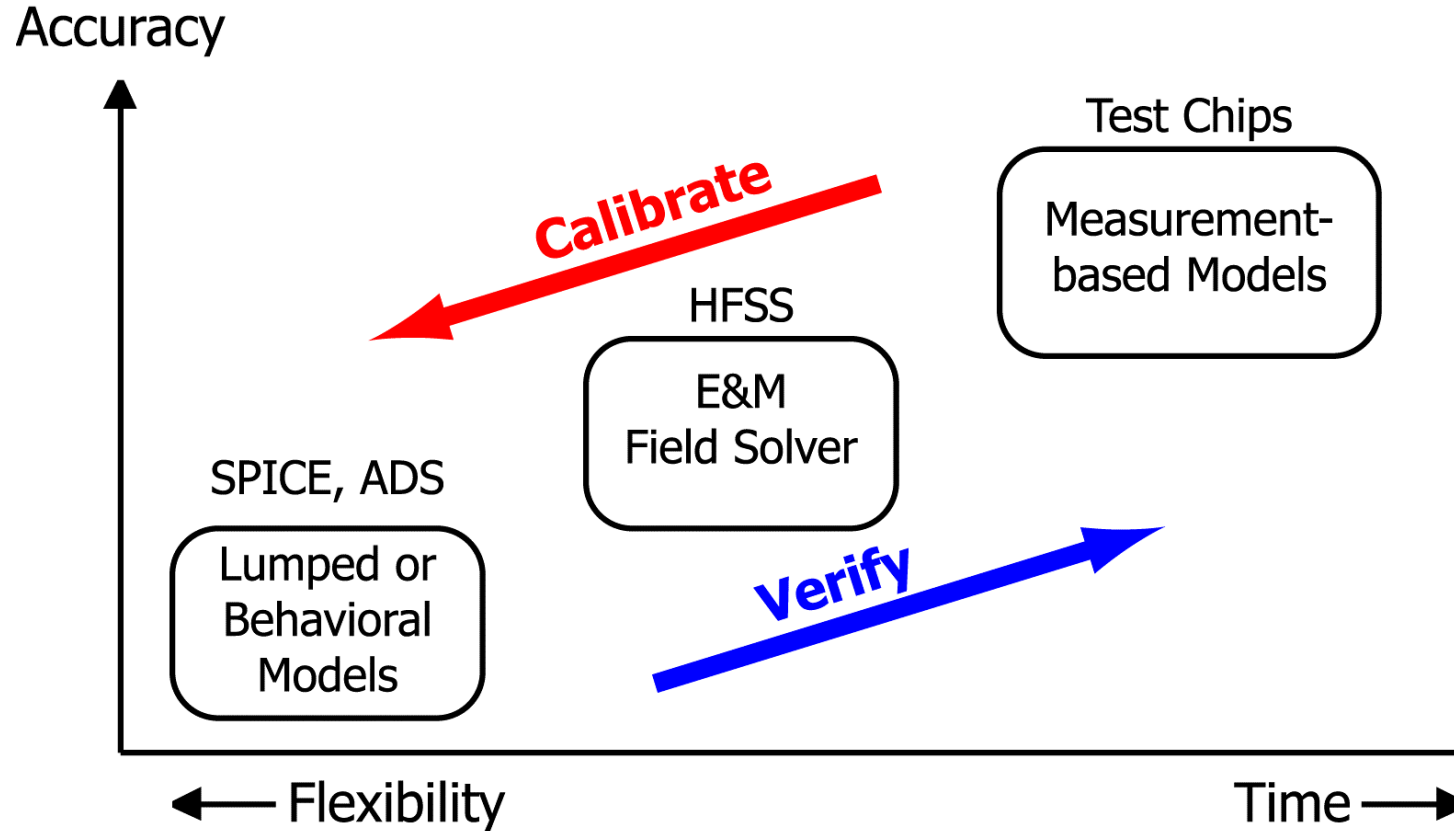
- 28 GHz LNA
- Embrace Distributed Circuit Elements

# Measurements at Microwave



De-embedding and calibration difficult  $\Rightarrow$   
Accurate measurements difficult to make above 20 GHz

# Compact Modeling Methodology



Calibrate and verify simpler models  
using most accurate data available

# Electromagnetism from Circuit Perspective

Consider the induced field  $E'$  due to an applied field  $E_0$

$$E = E_0 + E' = E_0 - \nabla\Phi - \frac{\partial A}{\partial t} = \frac{J}{\sigma}$$

Now integrate above expression over the conducting path

$$\int E_0 \cdot dl - \int \frac{J}{\sigma} \cdot dl - \int \frac{\partial A}{\partial t} \cdot dl - \int \nabla\Phi \cdot dl = 0$$

applied voltage

internal impedance

external inductance

capacitive term

# Insights from Maxwell's Equations

- From Maxwell's equations (Coulomb Gauge):

$$\begin{aligned}
 -\nabla^2 A &= j\omega\mu\epsilon E + \mu J = j\omega\mu\epsilon'(-j\omega A - \nabla\phi) \\
 &= \underbrace{\omega^2\mu\epsilon A}_{\text{radiation}} - \underbrace{j\omega\mu\sigma A}_{\text{eddy currents}} - \underbrace{j\omega\epsilon\mu\nabla\phi}_{\text{disp.}} - \underbrace{\mu\sigma\nabla\phi}_{\text{conduction}}
 \end{aligned}$$

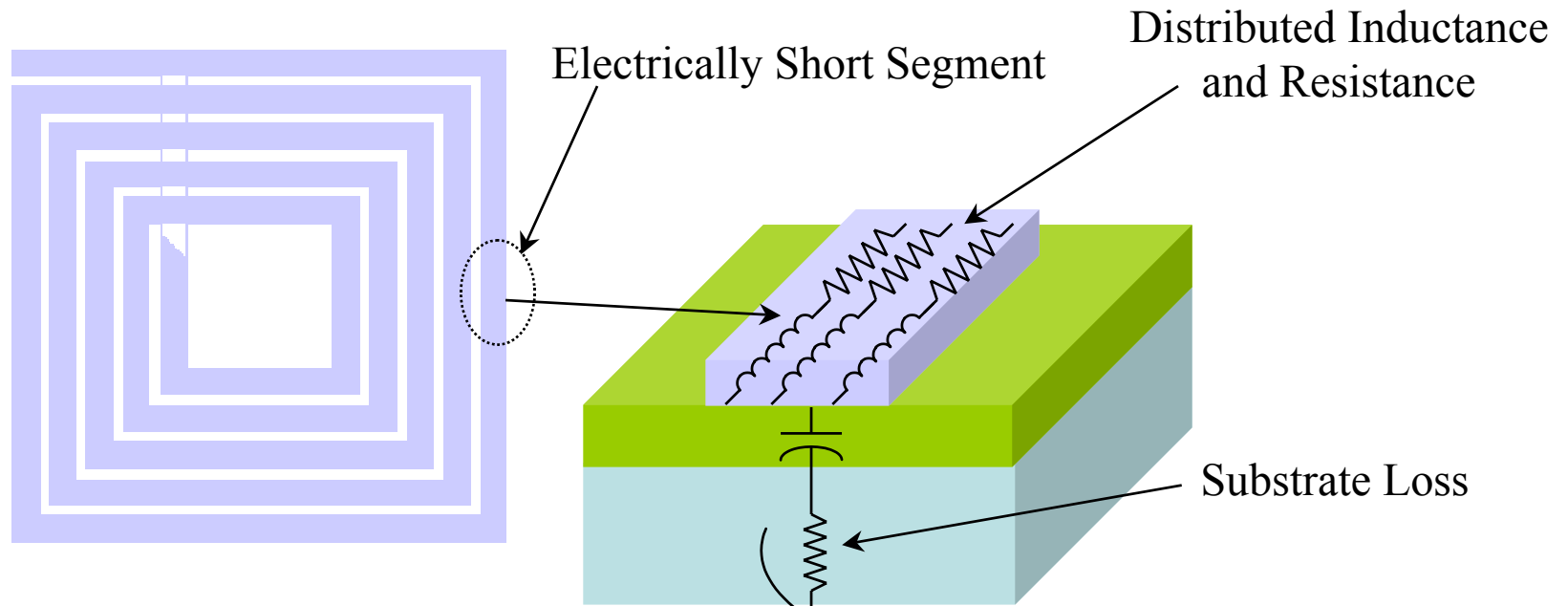
- Neglect radiation as long as  $l_{\max} \ll \lambda$
- Displacement and conduction current are curl-free
- Losses due to conduction currents accounted for by solving:

$$\nabla^2\phi = -\frac{\rho}{\epsilon'} \quad \epsilon' = \epsilon + \frac{j\sigma}{\omega}$$

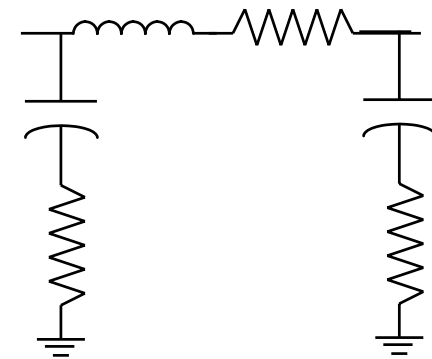
- Losses due to eddy currents accounted for by solving:

$$\nabla^2 A = j\omega\mu\sigma A$$

# PEEC Formulation



- Model short metal segment as lumped RLC Circuit
- Metal segments are linked capacitively and inductively
- Set up node equations for complete system and solve
- Method equivalent to solving Maxwell's Equations

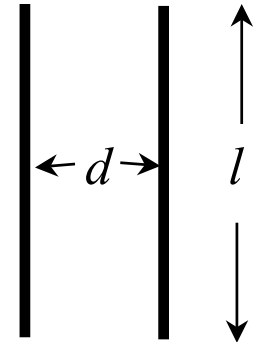


Reference: A. Ruehli, H. Heeb, *MTT*, July '92  
Partial Element Equivalent Circuits (*PEEC*)

# Analytic Inductance Computation

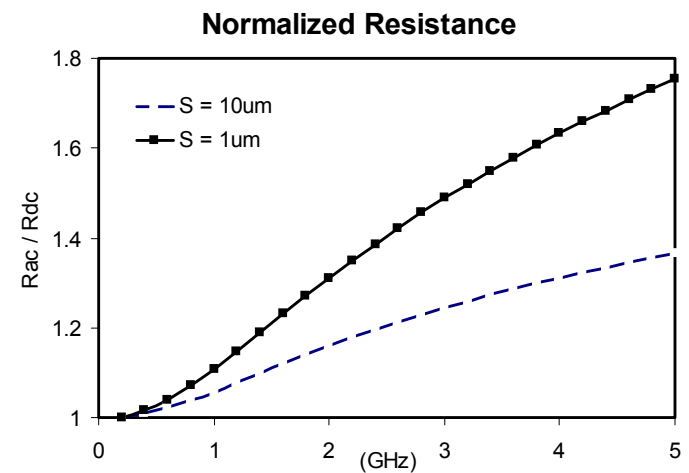
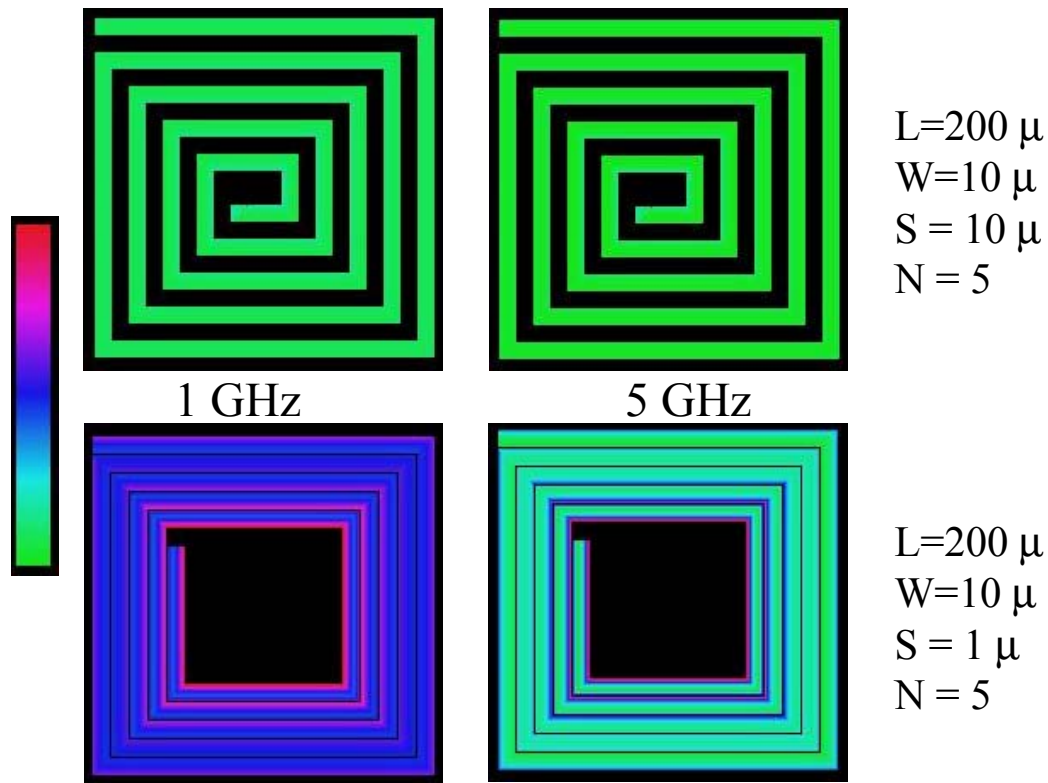
$$M(l, d) = 2 \times 10^{-4} \times l \times \left[ \ln \left( \sqrt{1 + \left( \frac{l}{d} \right)^2} + \frac{l}{d} \right) - \sqrt{1 + \left( \frac{d}{l} \right)^2} + \frac{d}{l} \right]$$

$$M \approx 2 \times 10^{-4} \times l \times \left( \frac{d}{l} - \ln(d) + \ln(2l) - 1 \right) \quad d/l \ll 1$$



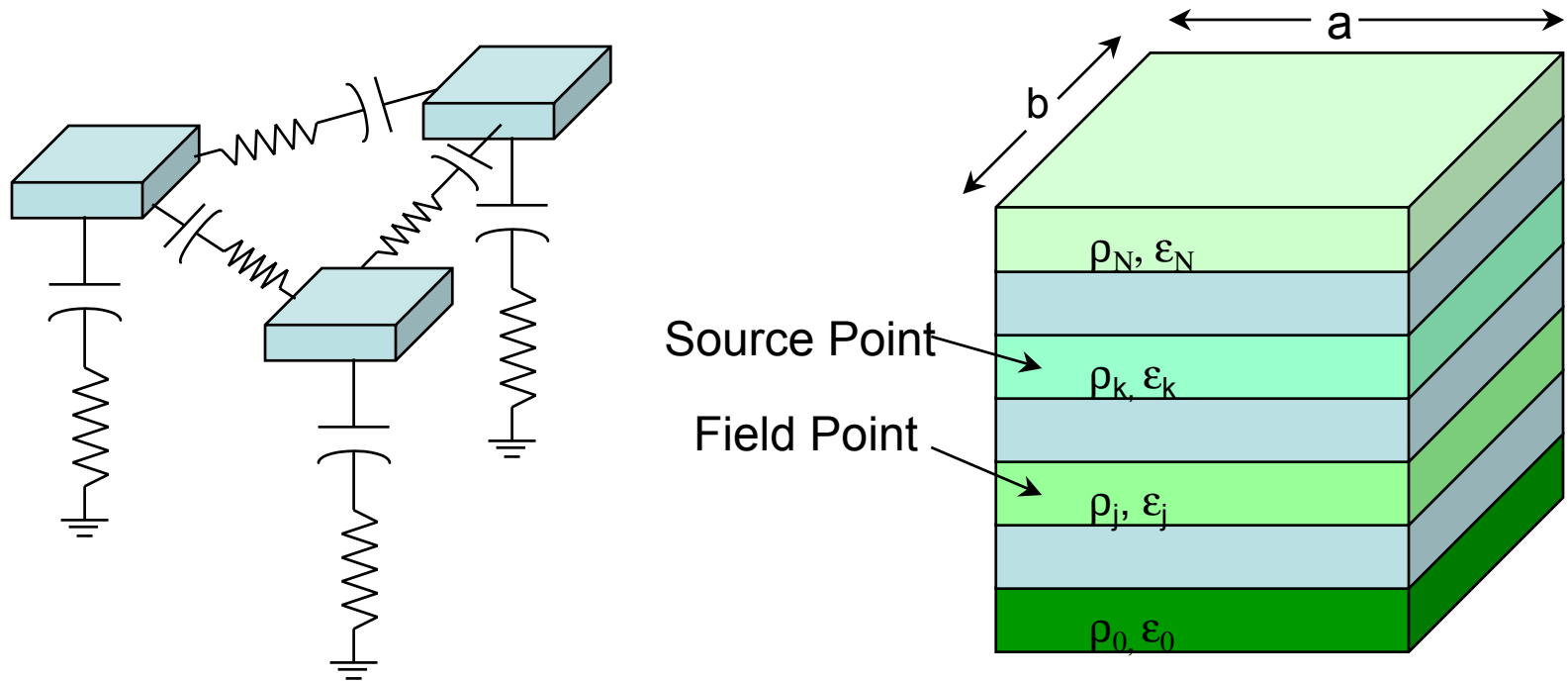
- Average  $\ln(d)$  over the cross section (*Geometric Mean Distance*)
- Can perform this integration for many cases of interest
- Symmetry arguments can be used to derive mutual inductance between non-equal-length filaments
- For non-parallel geometries can use filamental approximations

# Numerical Inductance Computation



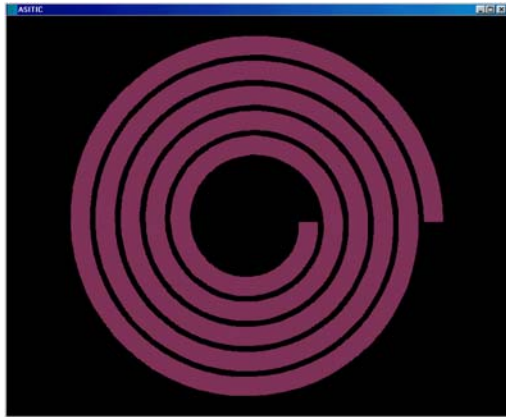
Numerical simulation captures skin-effect, proximity effect, and substrate-induced eddy current losses

# Capacitance Computation

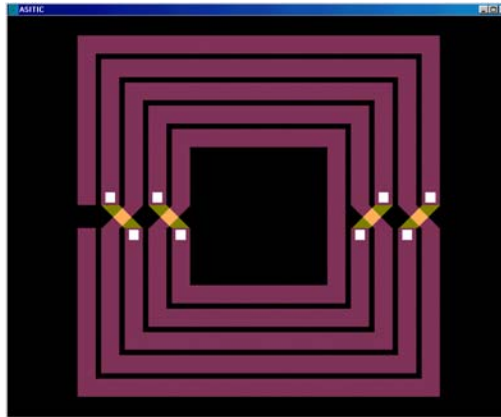


- Simple heuristic formulas don't take substrate into account
- A multi-layer Green function approach gives capacitive coupling impedance between metal layers on top of lossy Si substrate
- This computation is useful for passive devices (capacitors, inductors, transformers) as well as interconnect modeling and substrate loss

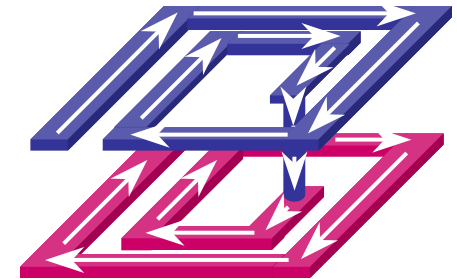
# Inductor Layout Options



Circular Spiral Inductor



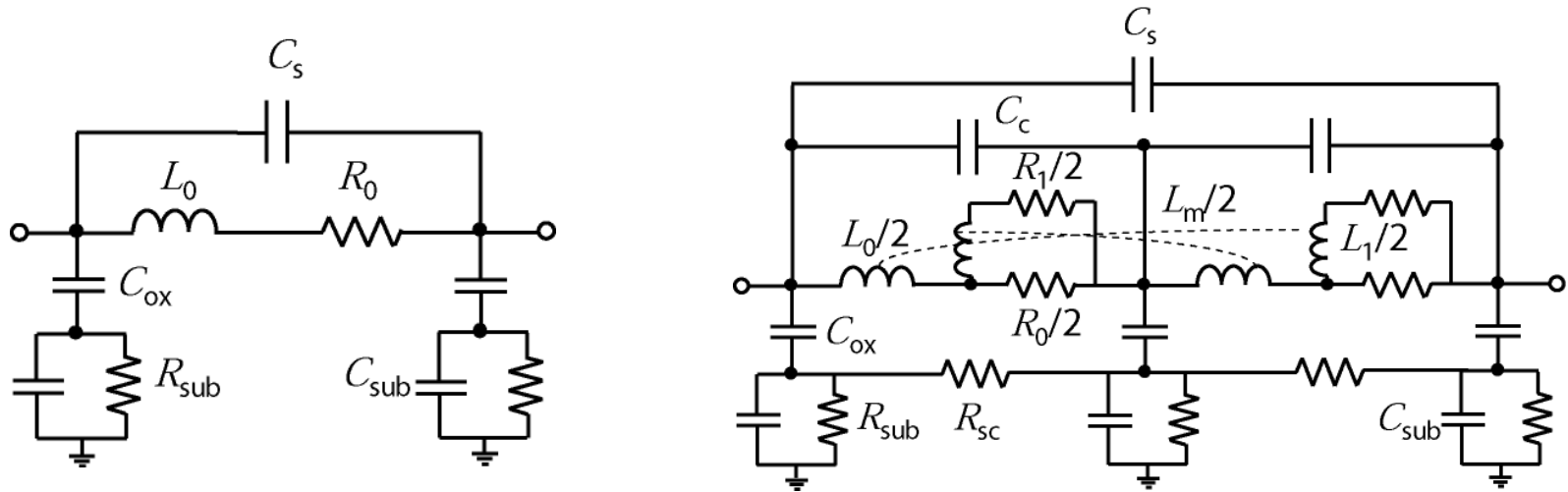
Symmetric Center-Tapped



3D Series Connected

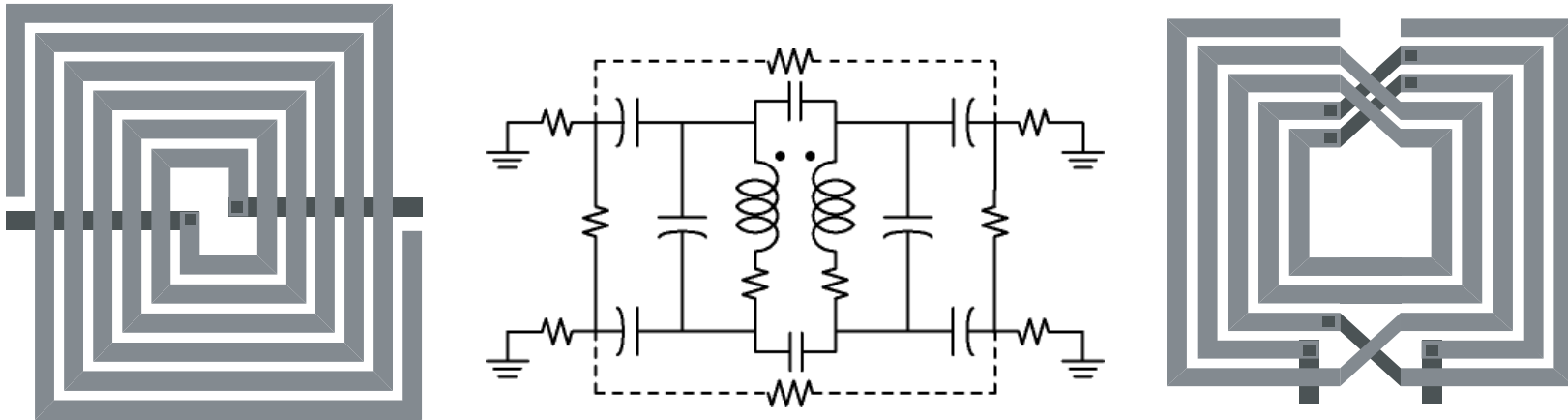
- Planar layout can be circular, square, polygon spirals, or “slabs”
- 3D layouts possible:
  - Shunt for low resistance
  - Series for high inductance
- Contact placement and shielding important options
- Diverse physical layout styles make analytical solutions difficult
- Foundry design kits often limit style and grounding options

# Inductor Compact Models



- Conventional  $\Pi$  model has physical roots
- Model works well over a narrow band
- Model cannot capture frequency-dependent skin-effect and proximity effects:  $L(f)$   $R(f)$
- Physically derived 2- $\Pi$  model can fit data over a wider frequency range

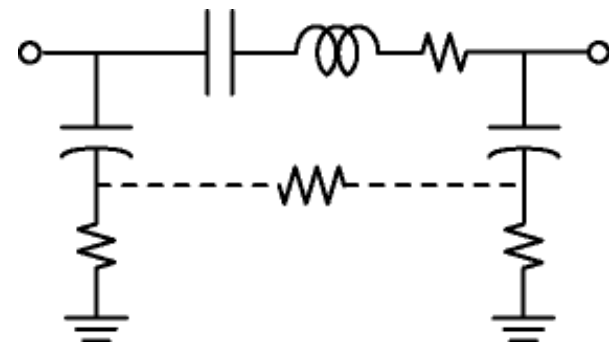
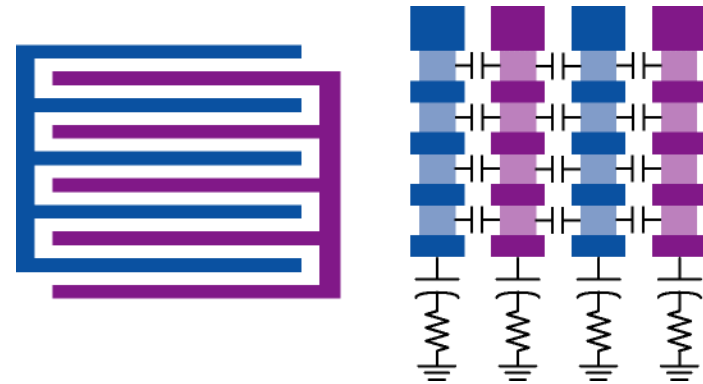
# Transformer Layout and Models



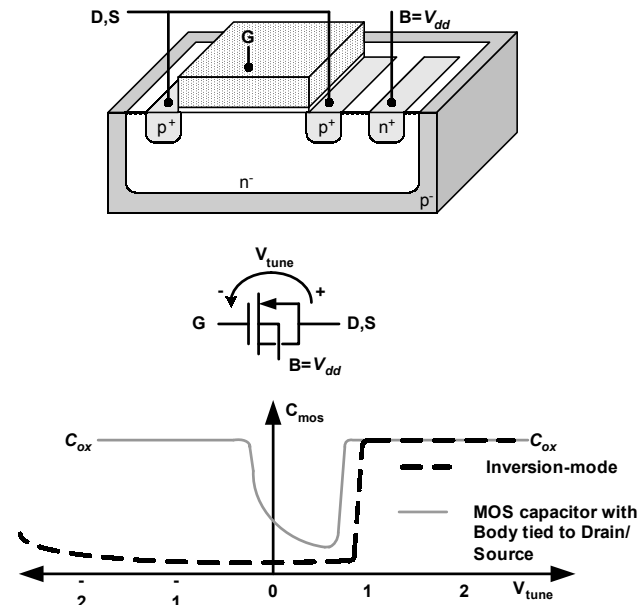
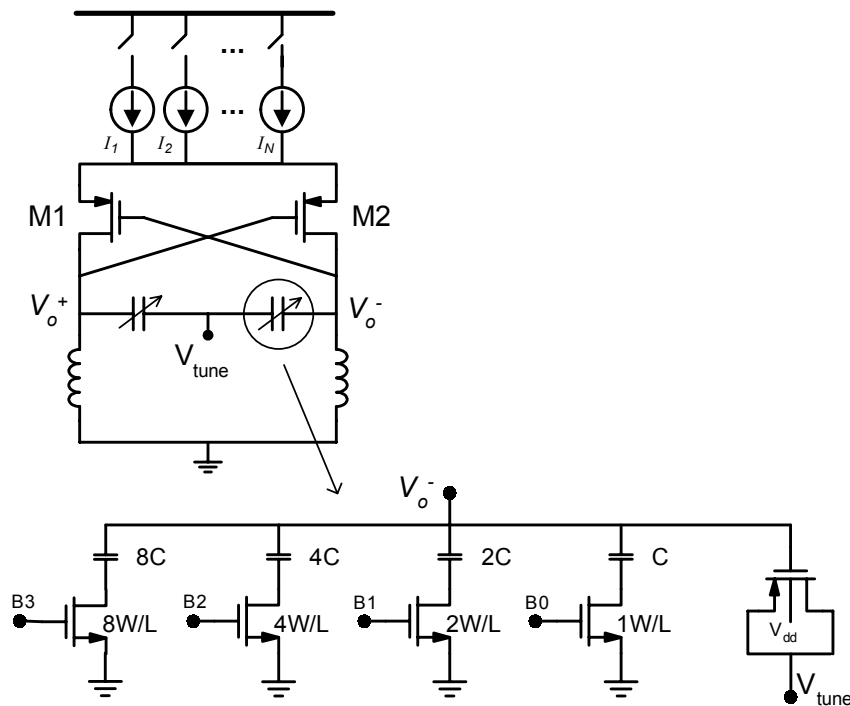
- Layout styles: square, polygon, circular, balanced, coupled lines
- To obtain turns ratio, can change width to alter inductance, skip turns on secondary, or put secondary turns in shunt (low loss)
- Modeling similar to inductor (self and mutual inductance)
- Phase balance between primary and secondary is important
  - Account for capacitive and substrate coupling between primary and secondary

# Capacitors and Varactors

- MIM capacitors are used for high Q applications
- Thin oxide MIM caps are usually an extra option → finger caps are a good alternative
- Varactors are important tuning elements
- MOS varactors require accurate CV-curve modeling of FETs
- Loss mechanism and parasitics:
  - distributed plate resistance
  - dielectric loss tangent
  - substrate parasitics
  - self-resonance



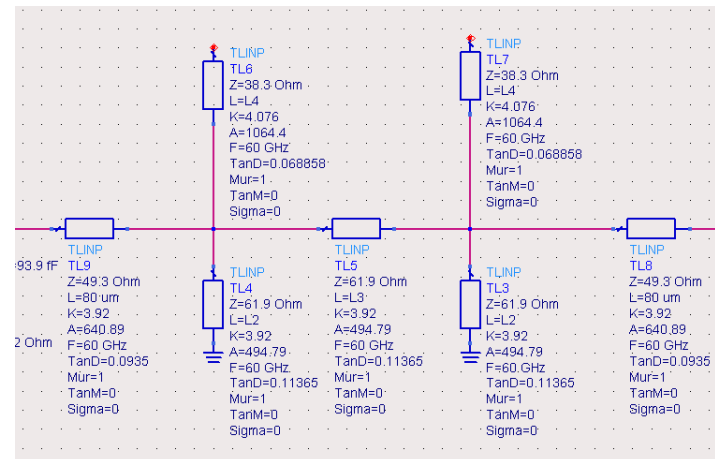
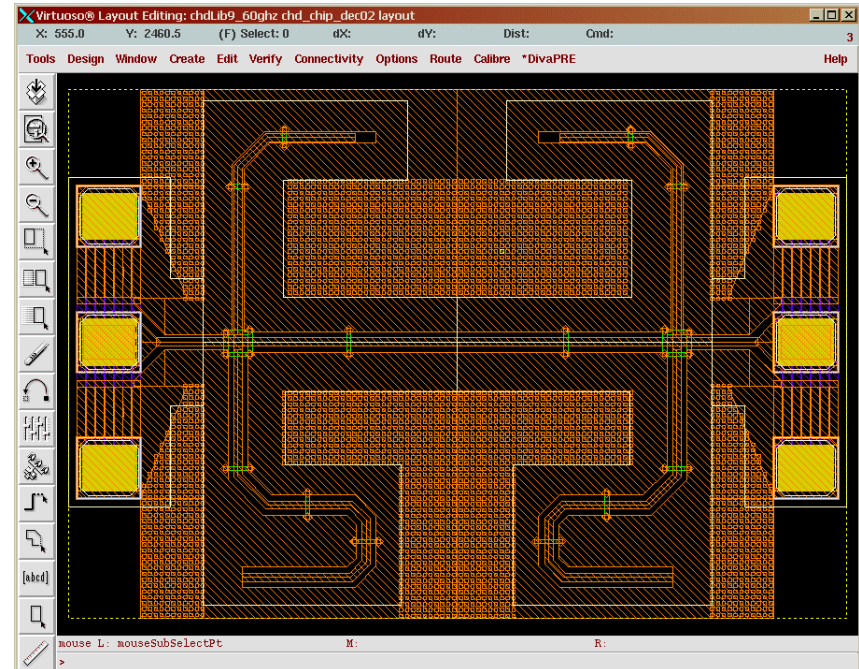
# MOS Switches and Varactors



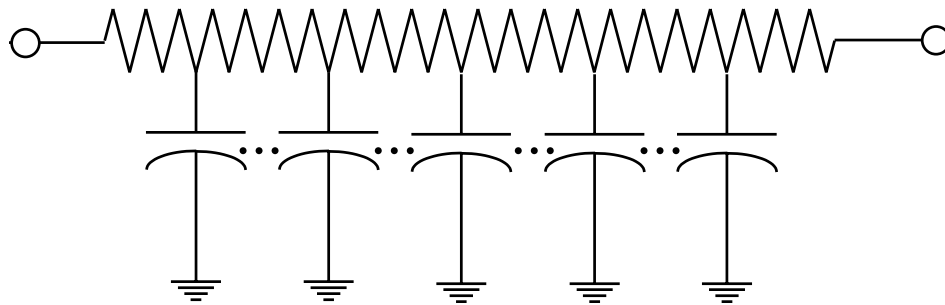
- MOS switches used as coarse tuning elements
- Need accurate models of MOS parasitics (limit on size of switch)
- MOS varactors or junction diode for fine control
- On-chip chokes or resistors to isolate tuning signal from tank

# Transmission Lines

- Transmission lines key microwave building blocks
- Only a few parameters characterize line:
  - Characteristic impedance
  - Propagation constant (loss and phase velocity)
- Analysis easier (2D), model inherently scalable in length
- Simulation of loss difficult in SPICE-type simulation



# IC Resistors at High Frequency

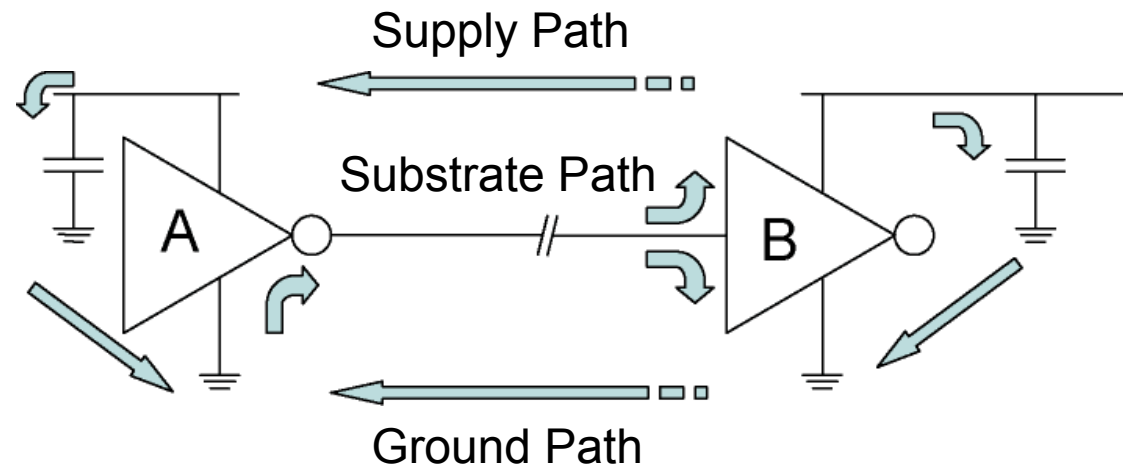


$$y_{11} = \sqrt{j\omega C_x / R} \coth \sqrt{j\omega R C_x}$$

$$y_{12} = -\sqrt{j\omega C_x / R} \operatorname{csch} \sqrt{j\omega R C_x}$$

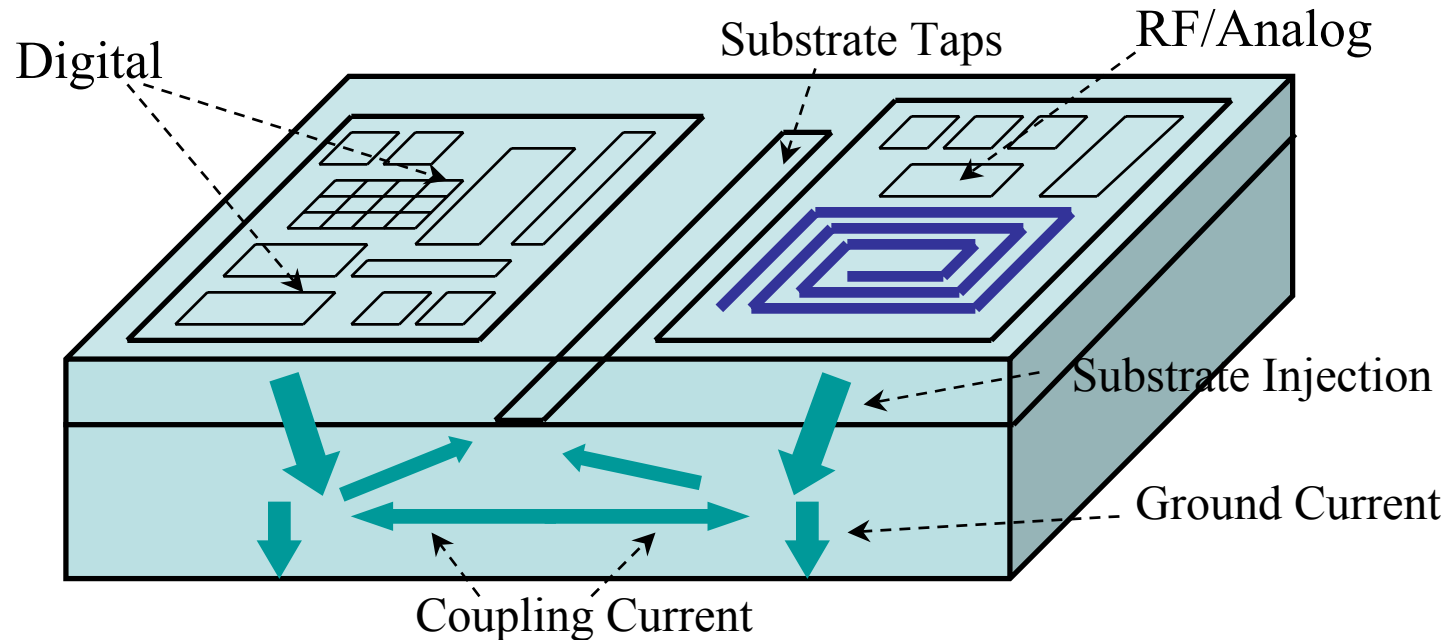
- High frequency resistors limited to thin-film or poly resistors with low capacitance
- Distributed capacitance important to model (RC line)
- MOS linear region devices make good variable resistors (should have accurate parasitics in FET model)
- Resistors less common due to RC pole limitations

# IC Interconnect Extraction



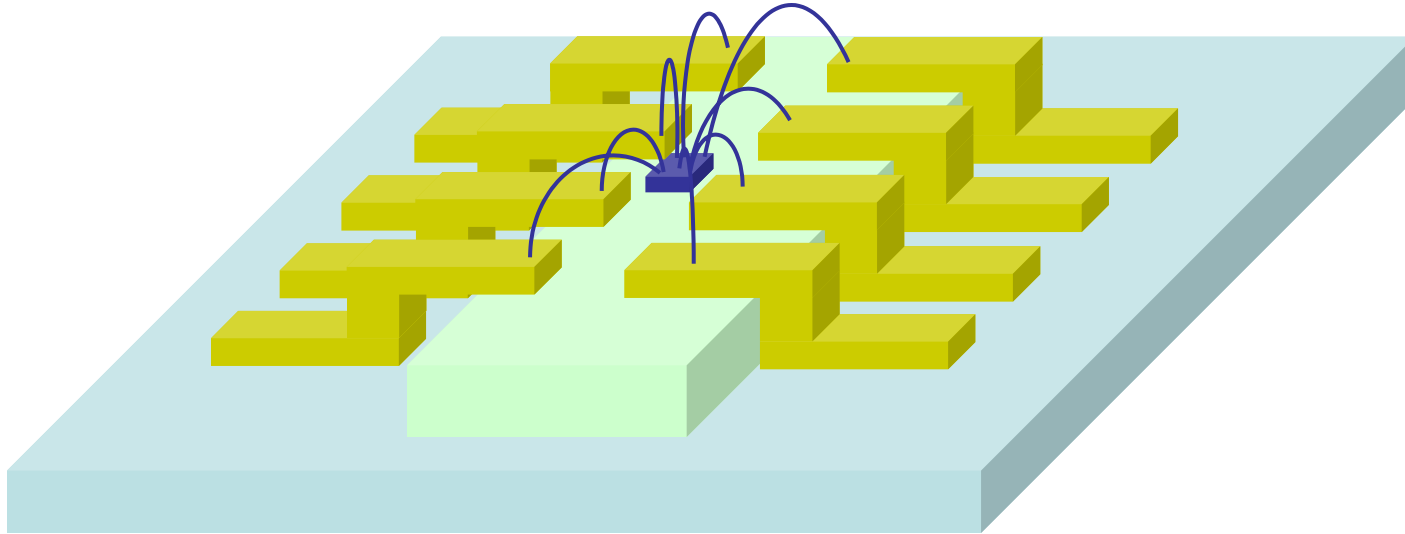
- Interconnect parasitics very important at RF and microwave frequencies
- Most parasitic interconnect extraction tools only compute capacitance and resistance
- Inductance extraction difficult due to the unknown and distributed “return current”
- Return current strong function of frequency: low frequency can even go off-chip!

# Substrate Coupling



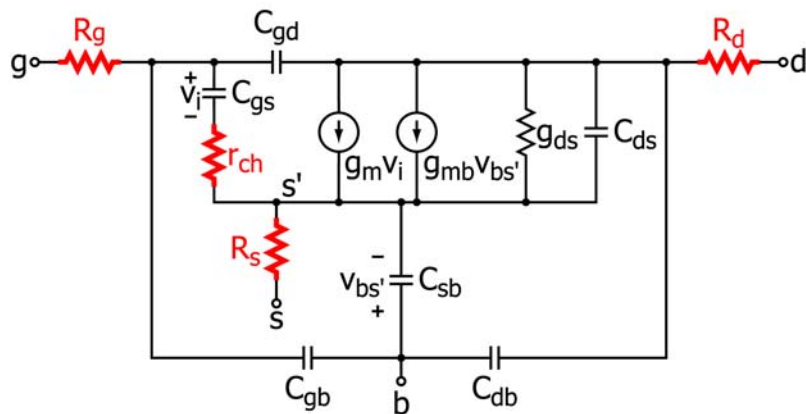
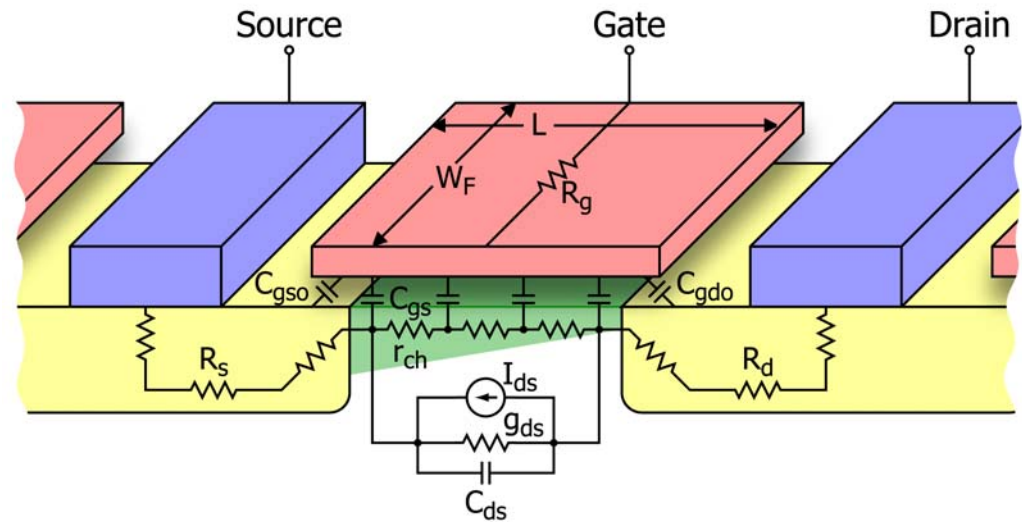
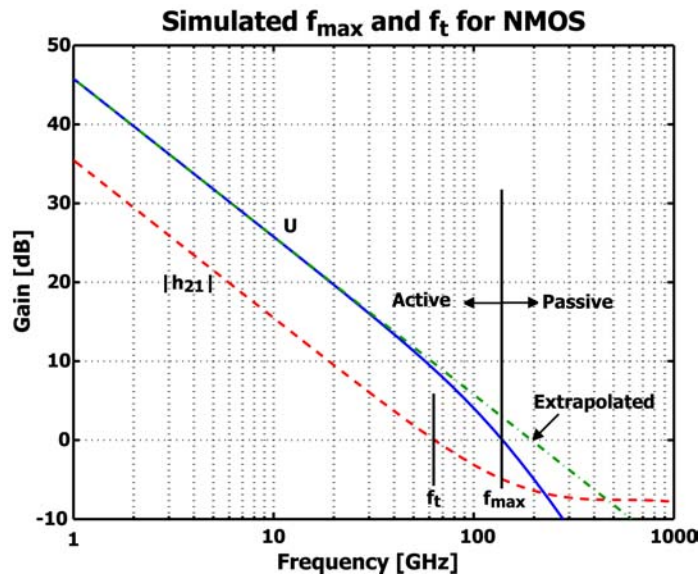
- Substrate coupling and loss important in mixed-signal ICs
- Digital circuits are pumping RF and microwave energy into substrate
- Quasi-static simulation is often performed, neglecting inductance effects
- Loss sets quality factor of passives and  $f_{\max}$  of actives

# Package and Board Level Parasitics



- Package parasitics important to model for RF signals going off-chip
- Package often limits isolation in circuits (accurate coupling)
- Co-simulation of chip + package + board difficult due to change of problem scale
- Higher frequency packages use flip-chip technology
- Many passive elements can be placed into package or board

# Active Device Limitations



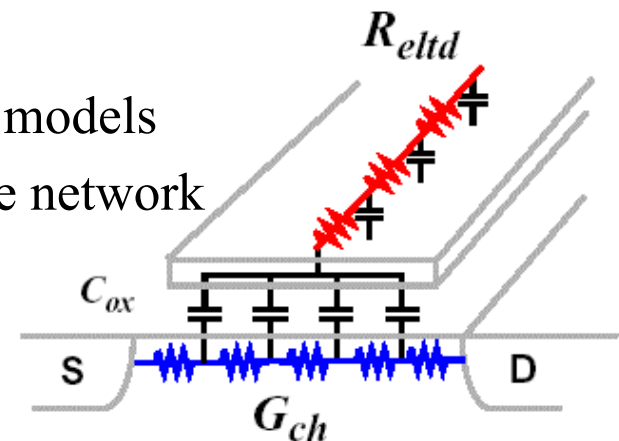
$$f_t \approx \frac{g_m}{2\pi C_{gg}}$$

$$f_{\max} \approx \frac{f_t}{2\sqrt{R_g(g_m C_{gd}/C_{gg}) + (R_g + r_{ch} + R_s)g_{ds}}}$$

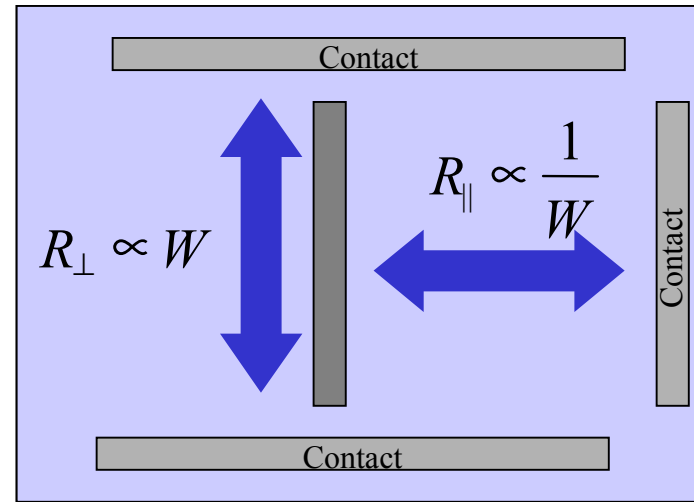
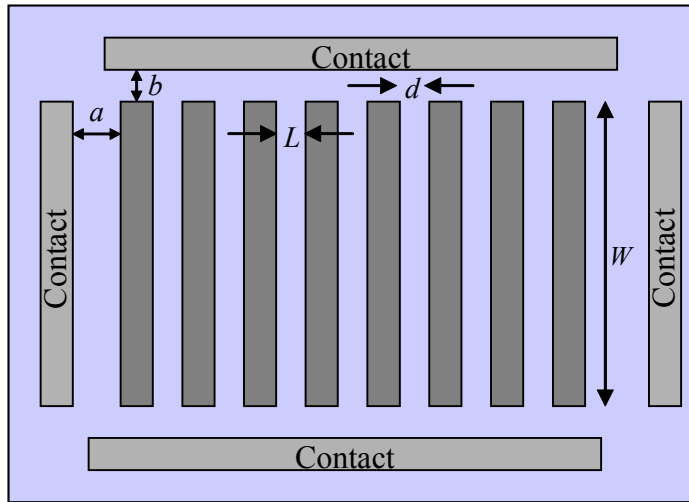
Test for passivity :  $U(f) < 1, \forall f > f_{\max}$

# Empirical vs. Physical Models

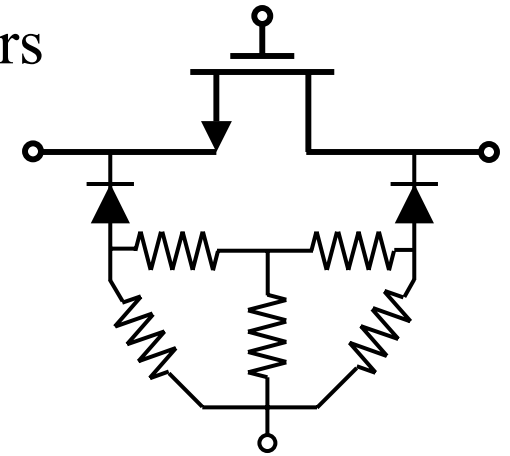
- Empirical approach:
  - A curve fitting problem exercise to all available measurement data
  - The table lookup is the extreme case of empirical compact model
    - ✗ Expansive in data collection
    - ✗ Cannot be used to calculate statistical variation
- BSIM4 RF relevant features:
  - Gate resistance is included in the core model
  - Improved non-quasi-static AC model
  - New noise-partition and holistic thermal noise models
  - A flexible and configurable substrate resistance network
  - Layout-dependent parasitic model



# FET Substrate Resistance



- Substrate limits high frequency gain of amplifiers
- Resistance adds excess thermal noise to circuit
- Coupling causes unwanted feedback and digital noise leakage into sensitive analog circuitry
- Scaling is non-trivial due to complex layout
- Need scaling equations for substrate network



# FET Distortion and Intermodulation

- Many RF and microwave circuits are non-linear or weakly non-linear
- Accurate distortion requires high accuracy in C-V and I-V curve *and* derivatives
- Device formulation should be as physical as possible to avoid numerical or unphysical distortion (symmetric MOSFET)

# Conclusion

- Passive devices play critical role at RF and microwave frequencies
- Accurate parasitic extraction needed for both active and passive devices
- Measurements difficult to perform at these frequencies ... need good analytical and numerical framework
- Accurate substrate extraction and scaling is a recurring theme

# Acknowledgements

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- STMicroelectronics
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- CMC